

12-6-03

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
PROJECTED ITERATIONS: BATCH **COMPLETE**
PROJECTED ANSWERS: 1 TO 80
1 TO 80

L4 1 SEA SSS SAM L2 AND L1

=> d

L4 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS on STN
RN 474510-67-3 REGISTRY
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 3-hydroxytricyclo[3.3.1.13.7]dec-1-yl ester, polymer with 1-bicyclo[2.2.1]hept-5-en-2-yl-2-methyl-2-(4-methylcyclohexyl)-1-propanone, 5-ethoxy-3a,4,5,6,7,7a-hexahydro-4,7-methano-1H-indene and 2,5-furandione (SCI) (CA INDEX NAME)

MF (C18 H28 O . C18 H24 O3 . C12 H18 O . C4 H2 O3)x

CI PMS

PCT Polyether, Polyvinyl

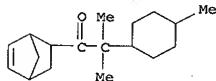
SR CA

LC STN Files: CA, CAPLUS

CM 1

CRN 474510-66-2

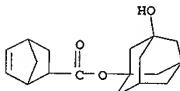
CMF C18 H28 O



CM 2

CRN 331866-92-3

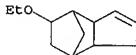
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CM 3

CRN 53018-26-1

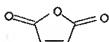
CMF C12 H18 O



CM 4

CRN 108-31-6

CMF C4 H2 O3



1 REFERENCES IN FILE CA (1907 TO DATE)

1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FIL HCAPLUS, CAPLUS, USPATFULL
COST IN U.S. DOLLARS

SINCE FILE
ENTRY

TOTAL
SESSION

FULL ESTIMATED COST

2.08

2.29

FILE 'HCAPLUS' ENTERED AT 15:29:53 ON 05 DEC 2003
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FILE 'USPATFULL' ENTERED AT 15:29:53 ON 05 DEC 2003
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=> s 14

L5 2 L4

=> d 15 1-2 ibib hitstr

L5 ANSWER 1 OF 2 HCAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2002848220 HCAPLUS
DOCUMENT NUMBER: 137:360306
TITLE: Radiation-sensitive positively working photosensitive
composition
INVENTOR(S): Kodama, Kunihiko; Sato, Kenichiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 92 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002323758	A2	20021108	JP 2001-157367	20010525
US 2003017415	A1	20030123	US 2002-79414	20020222
PRIORITY APPLN. INFO.:				
		JP 2001-48783	A	20010223
		JP 2001-48602	A	20010223
		JP 2001-48784	A	20010223
		JP 2001-48880	A	20010223
		JP 2001-157366	A	20010525
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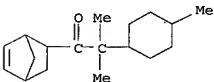
IT 474510-67-3P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)
(radiation-sensitive pos. working photosensitive compn. for high
resoln. and storage stability)

RN 474510-67-3 HCAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 3-
hydroxytricyclo[3.3.1.13.7]dec-1-yl ester, polymer with
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2,5-furandione (9CI) (CA INDEX NAME)

CM 1

CRN 474510-66-2

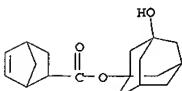
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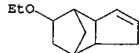
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CMF C18 H24 O3



CM 3

CRN 53018-26-1
CMF C12 H18 O



CM 4

CRN 108-31-6
CMF C4 H2 O3



L5 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2003 ACS on STN
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DOCUMENT NUMBER: 137:360306
TITLE: Radiation-sensitive positively working photosensitive composition
INVENTOR(S): Kodama, Kunihiko; Sato, Kenichiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 92 pp.
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DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

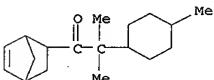
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			JP 2001-48784	A 20010223
			JP 2001-48880	A 20010223
			JP 2001-157366	A 20010525
			JP 2001-157367	A 20010525

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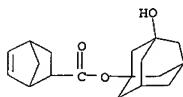
CM 1

CRN 474510-66-2
CMF C18 H28 O



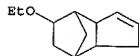
CM 2

CRN 331866-92-3
CMF C18 H24 O3



CM 3

CRN 53018-26-1
CMF C12 H18 O



CM 4

CRN 108-31-6
CMF C4 H2 O3

